## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

:

Jyun IWASHITA et al.

Mail Stop: PCT

Serial No. 10/549,849

Attorney Docket No. 2005 1513A

Filed September 23, 2005

NEGATIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN [Corresponding to PCT/JP2004/004080 Filed March 24, 2004]

## SECOND INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to the provisions of 37 CFR 1.56, 1.97 and 1.98, Applicants request consideration of the references listed on attached form PTO-1449 and any additional information identified below in paragraph 3. A legible copy of each reference listed on the Form PTO-1449 is enclosed, except a copy is not provided for:

	[]	each U.S. Patent and U.S. Patent application publication;					
	D	each reference previously cited in the international application PCT/; and/or					
	O	each reference previously cited in prior parent application Serial No.					
la.	[X] This Information Disclosure Statement is submitted:						
	within three months of the filing date (or of entry into the National Stage) of the above-entitled application, or						

before the mailing of a first Office Action on the merits or the mailing of a first Office Action after the filing of an RCE,

## and thus no certification and/or fee is required.

1b. [] This Information Disclosure Statement is submitted

after the events of above paragraph 1a and prior to the mailing date of a final Office Action or a Notice of Allowance or an action which otherwise closes prosecution in the application, and thus:

- (1) [] the certification of paragraph 2 below is provided, or
- (2) [] the fee of \$180.00 specified in 37 CFR 1.17(p) is enclosed.
- 1c. [] This Information Disclosure Statement is submitted:

after the mailing date of a final Office Action or Notice of Allowance or action which otherwise closes prosecution in the application, and prior to payment of the issue fee, and thus:

the certification of paragraph 2 below is provided, and

the fee of \$180.00 specified in 37 CFR 1.17(p) is enclosed.

- 2. It is hereby certified
  - a. [] that each item of information contained in this Information Disclosure

    Statement was first cited in any communication from a foreign patent office in a

    counterpart foreign application not more than three months prior to the filing of
    the Statement, or
  - b. [] that no item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application and, to the knowledge of the person signing the certification after making reasonable inquiry, was known to any individual designated in §1.56(c) more than three months prior to the filing of the Statement.

- Consideration of the following list of additional information (including any copending or abandoned U.S. application, prior uses and/or sales, etc.) is requested.
- 4. For each non-English language reference listed on the attached form PTO-1449, reference is made to:
  - a. [X] a full or partial English language translation submitted herewith,
  - b. [] a foreign patent office search report (in the English language) submitted herewith,
  - the concise explanation contained in the specification of the present application c. [X] at pages 1 to 3,
  - d. [] the concise explanation set forth in the attached English language abstract,
  - e. [] the concise explanation set forth below or on a separate sheet attached to the reference:
- 5. [] A foreign patent office search report citing one or more of the references is enclosed.

Respectfully submitted,

Jyun IWASHITA et al.

By

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THE COMMISSIONER IS AUTHORIZED
TO CHARGE TO DEFICIENCY IN THE
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December 12, 2005

Sheet 1 of 1 ' INFORMATION DISCLOSURE STATEMENT												
FORM PTO 1449 (1	ATTY DOCKET NO. 2005_1513A		SERIAL NO. 10/549,849									
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Date S	FILING DATE September 23, 2005				GROUP							
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	AP	Maeda, K. et al., "ArF Chemically Amplified Negative Resist Using Alicyclic Epoxy Polymer", <i>Journal of Photopolymer Science and Technology</i> , Vol. 11, No. 3, pp. 507 to 512 (1998).										
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EXAMINER					DATE CONSIDERED							